

# [COLOR FILTER SUBSTRATE AND FABRICATING METHOD THEREOF]

## Abstract

A method of fabricating a color filter substrate is described. A black matrix is formed on a substrate. A color photoresist is formed for covering the black matrix. A photomask is located over the substrate, and then an exposure process is performed. The photomask comprises a transparent region, a partial transparent region and a no-transparent region, wherein the partial transparent region is located between the transparent region and the no-transparent region and is also located at the edge of the black matrix. A development process is performed for patterning the color photoresist. Since the exposure process is performed with the photomask via the partial transparent region, the issue that the height difference exists at the edge of the black matrix due to using black resin can be resolved.